

Kenichiro Mizohata

List of Publications by Year in Descending Order

Source: <https://exaly.com/author-pdf/7996254/kenichiro-mizohata-publications-by-year.pdf>

Version: 2024-04-20

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.

The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

103
papers

1,337
citations

22
h-index

29
g-index

108
ext. papers

1,647
ext. citations

5.2
avg, IF

4.63
L-index

#	Paper	IF	Citations
103	Two-step implantation of gold into graphene. <i>2D Materials</i> , 2022 , 9, 025011	5.9	1
102	Atomic layer deposition of GdF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022 , 40, 022402	2.9	0
101	Thermal diffusivity recovery and defect annealing kinetics of self-ion implanted tungsten probed by insitu Transient Grating Spectroscopy. <i>Acta Materialia</i> , 2022 , 117926	8.4	2
100	High-fidelity patterning of AlN and ScAlN thin films with wet chemical etching. <i>Materialia</i> , 2022 , 22, 101403	5.0	0
99	From lakes to ratios: 14C measurement process of the Finnish tree-ring research consortium. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2022 , 519, 37-45	1.2	0
98	Laser induced breakdown spectroscopy for hydrogen detection in molybdenum at atmospheric pressure mixtures of argon and nitrogen. <i>Fusion Engineering and Design</i> , 2022 , 179, 113131	1.7	0
97	In-situ plasma treatment of Cu surfaces for reducing the generation of vacuum arc breakdowns. <i>Journal of Applied Physics</i> , 2021 , 130, 143302	2.5	0
96	Comparative study of deuterium retention and vacancy content of self-ion irradiated tungsten. <i>Journal of Nuclear Materials</i> , 2021 , 153373	3.3	3
95	VOLUMES OF WORTH DELIMITING THE SAMPLE SIZE FOR RADIOCARBON DATING OF PARCHMENT. <i>Radiocarbon</i> , 2021 , 63, 105-120	4.6	2
94	Observed and Modeled Black Carbon Deposition and Sources in the Western Russian Arctic 1800-2014. <i>Environmental Science & Technology</i> , 2021 , 55, 4368-4377	10.3	1
93	Atomic layer deposition of TbF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021 , 39, 022404	2.9	2
92	Highly Material Selective and Self-Aligned Photo-assisted Atomic Layer Deposition of Copper on Oxide Materials. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2100014	4.6	3
91	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. <i>Dalton Transactions</i> , 2021 , 50, 13264-13275	4.3	0
90	Enhancement of vacancy diffusion by C and N interstitials in the equiatomic FeMnNiCoCr high entropy alloy. <i>Acta Materialia</i> , 2021 , 215, 117093	8.4	7
89	Understanding the Stabilizing Effects of Nanoscale Metal Oxide and Li-Metal Oxide Coatings on Lithium-Ion Battery Positive Electrode Materials. <i>ACS Applied Materials & Interfaces</i> , 2021 , 13, 42773-42790	9.5	6
88	New perspectives on collision cascade damage in self-ion irradiated tungsten from HR-EBSD and ECCI. <i>Journal of Nuclear Materials</i> , 2021 , 554, 153074	3.3	0
87	Observation of Transient and Asymptotic Driven Structural States of Tungsten Exposed to Radiation. <i>Physical Review Letters</i> , 2020 , 125, 225503	7.4	13

86	Charge state optimisation for beryllium accelerator mass spectrometry. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2020 , 469, 33-36	1.2	0
85	Nanoscale lattice strains in self-ion implanted tungsten. <i>Acta Materialia</i> , 2020 , 195, 219-228	8.4	14
84	Magnetic properties and resistive switching in mixture films and nanolaminates consisting of iron and silicon oxides grown by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020 , 38, 042405	2.9	2
83	Hydrogen isotope exchange mechanism in tungsten studied by ERDA. <i>Physica Scripta</i> , 2020 , T171, 0140566	6.6	1
82	Thermal diffusivity degradation and point defect density in self-ion implanted tungsten. <i>Acta Materialia</i> , 2020 , 193, 270-279	8.4	22
81	Effect of interstitial carbon on the evolution of early-stage irradiation damage in equi-atomic FeMnNiCoCr high-entropy alloys. <i>Journal of Applied Physics</i> , 2020 , 127, 025103	2.5	13
80	Silicon oxide-niobium oxide mixture films and nanolaminates grown by atomic layer deposition from niobium pentaethoxide and hexakis(ethylamino) disilane. <i>Nanotechnology</i> , 2020 , 31, 195713	3.4	3
79	Comparative study of deuterium retention in irradiated Eurofer and FeCr from a new ion implantation materials facility. <i>Nuclear Fusion</i> , 2020 , 60, 016024	3.3	7
78	Ionic conductivity in Li_xTaO_y thin films grown by atomic layer deposition. <i>Electrochimica Acta</i> , 2020 , 361, 137019	6.7	3
77	Characterising Ion-Irradiated FeCr: Hardness, Thermal Diffusivity and Lattice Strain. <i>Acta Materialia</i> , 2020 , 201, 535-546	8.4	5
76	Modified deformation behaviour of self-ion irradiated tungsten: A combined nano-indentation, HR-EBSD and crystal plasticity study. <i>International Journal of Plasticity</i> , 2020 , 135, 102817	7.6	11
75	Atomic Layer Deposition of PbS Thin Films at Low Temperatures. <i>Chemistry of Materials</i> , 2020 , 32, 8216-8228	8.2	7
74	Optical characteristics of virgin and proton-irradiated ceramics of magnesium aluminate spinel. <i>Optical Materials</i> , 2019 , 96, 109308	3.3	13
73	Charge carrier dynamics in tantalum oxide overlayered and tantalum doped hematite photoanodes. <i>Journal of Materials Chemistry A</i> , 2019 , 7, 3206-3215	13	15
72	Comparative study on the use of novel heteroleptic cyclopentadienyl-based zirconium precursors with H ₂ O and O ₃ for atomic layer deposition of ZrO ₂ . <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020912	2.9	2
71	Intercalation of Lithium Ions from Gaseous Precursors into EMnO_2 Thin Films Deposited by Atomic Layer Deposition. <i>Journal of Physical Chemistry C</i> , 2019 , 123, 15802-15814	3.8	9
70	Direct observation of mono-vacancy and self-interstitial recovery in tungsten. <i>APL Materials</i> , 2019 , 7, 021103	5.7	25
69	Deposition of impurity metals during campaigns with the JET ITER-like Wall. <i>Nuclear Materials and Energy</i> , 2019 , 19, 218-224	2.1	14

68	Studies on solid state reactions of atomic layer deposited thin films of lithium carbonate with hafnia and zirconia. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020929	2.9	5
67	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl ₂ (TMPDA) and Tert-Butylhydrazine as Precursors. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2019 , 216, 1900058	1.6	4
66	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020921	2.9	10
65	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS ₂ and ZrS ₂ , for Optoelectronics. <i>Chemistry of Materials</i> , 2019 , 31, 5713-5724	9.6	36
64	Atomic Layer Deposition of Photoconductive CuO Thin Films. <i>ACS Omega</i> , 2019 , 4, 11205-11214	3.9	19
63	Nickel Germanide Thin Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2019 , 31, 5314-5319	9.6	5
62	Toward epitaxial ternary oxide multilayer device stacks by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020602	2.9	3
61	Photoassisted atomic layer deposition of oxides employing alkoxides as single-source precursors. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 060911	2.9	5
60	Atomic layer deposition of cobalt(II) oxide thin films from Co(BTSA) ₂ (THF) and H ₂ O. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 010908	2.9	1
59	Atomic Layer Deposition of PbI ₂ Thin Films. <i>Chemistry of Materials</i> , 2019 , 31, 1101-1109	9.6	34
58	Atomic Layer Deposition of Intermetallic Co ₃ Sn ₂ and Ni ₃ Sn ₂ Thin Films. <i>Advanced Materials Interfaces</i> , 2019 , 6, 1801291	4.6	8
57	Hydrogen isotope exchange in tungsten during annealing in hydrogen atmosphere. <i>Nuclear Fusion</i> , 2019 , 59, 026016	3.3	11
56	Tracing grog and pots to reveal Neolithic Corded Ware Culture contacts in the Baltic Sea region (SEM-EDS, PIXE). <i>Journal of Archaeological Science</i> , 2018 , 91, 77-91	2.9	17
55	Atomic Layer Deposition of Rhenium Disulfide. <i>Advanced Materials</i> , 2018 , 30, e1703622	24	45
54	Atomic Layer Deposition of Zirconium Dioxide from Zirconium Tetraiodide and Ozone. <i>ECS Journal of Solid State Science and Technology</i> , 2018 , 7, P1-P8	2	3
53	Atomic layer deposition of lanthanum oxide with heteroleptic cyclopentadienyl-amidinate lanthanum precursor - Effect of the oxygen source on the film growth and properties. <i>Thin Solid Films</i> , 2018 , 660, 199-206	2.2	7
52	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie</i> , 2018 , 130, 14746-14750	3.6	2
51	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie - International Edition</i> , 2018 , 57, 14538-14542	16.4	16

50	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. <i>Chemistry of Materials</i> , 2018 , 30, 3499-3507 ²¹	9.6	21
49	Effect of Au ion beam on structural, surface, optical and electrical properties of ZnO thin films prepared by RF sputtering. <i>Ceramics International</i> , 2018 , 44, 16464-16469	5.1	9
48	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. <i>Chemistry of Materials</i> , 2018 , 30, 8690-8701	9.6	16
47	Atomic layer deposition of crystalline molybdenum oxide thin films and phase control by post-deposition annealing. <i>Materials Today Chemistry</i> , 2018 , 9, 17-27	6.2	22
46	Preparation of Lithium Containing Oxides by the Solid State Reaction of Atomic Layer Deposited Thin Films. <i>Chemistry of Materials</i> , 2017 , 29, 998-1005	9.6	11
45	Studies on Thermal Atomic Layer Deposition of Silver Thin Films. <i>Chemistry of Materials</i> , 2017 , 29, 2040-2045	9.6	23
44	Atomic layer deposition and properties of mixed Ta ₂ O ₅ and ZrO ₂ films. <i>AIP Advances</i> , 2017 , 7, 025001	1.5	21
43	Potential gold(I) precursors evaluated for atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 01B112	2.9	13
42	Studies on Li ₃ AlF ₆ thin film deposition utilizing conversion reactions of thin films. <i>Thin Solid Films</i> , 2017 , 636, 26-33	2.2	5
41	Atomic Layer Deposition of Crystalline MoS ₂ Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700123	4.6	75
40	As ₂ S ₃ thin films deposited by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 01B114	2.9	8
39	(Invited) Photo-Assisted ALD: Process Development and Application Perspectives. <i>ECS Transactions</i> , 2017 , 80, 49-60	1	7
38	Instability of the Sb vacancy in GaSb. <i>Physical Review B</i> , 2017 , 95,	3.3	12
37	Atomic Layer Deposition of Zinc Glutarate Thin Films. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700512	4.6	2
36	Low-Temperature Atomic Layer Deposition of Low-Resistivity Copper Thin Films Using Cu(dmap) ₂ and Tertiary Butyl Hydrazine. <i>Chemistry of Materials</i> , 2017 , 29, 6502-6510	9.6	18
35	Low-Temperature Atomic Layer Deposition of Cobalt Oxide as an Effective Catalyst for Photoelectrochemical Water-Splitting Devices. <i>Chemistry of Materials</i> , 2017 , 29, 5796-5805	9.6	32
34	Thermal Atomic Layer Deposition of Continuous and Highly Conducting Gold Thin Films. <i>Chemistry of Materials</i> , 2017 , 29, 6130-6136	9.6	25
33	Bismuth iron oxide thin films using atomic layer deposition of alternating bismuth oxide and iron oxide layers. <i>Thin Solid Films</i> , 2016 , 611, 78-87	2.2	16

32	Atomic layer deposition of aluminum oxide on modified steel substrates. <i>Surface and Coatings Technology</i> , 2016 , 304, 1-8	4.4	10
31	Electric and Magnetic Properties of ALD-Grown BiFeO ₃ Films. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 7313-7322	3.8	25
30	Radiation resistance diagnostics of wide-gap optical materials. <i>Optical Materials</i> , 2016 , 55, 164-167	3.3	28
29	Alkylsilyl compounds as enablers of atomic layer deposition: analysis of (Et ₃ Si) ₃ As through the GaAs process. <i>Journal of Materials Chemistry C</i> , 2016 , 4, 449-454	7.1	2
28	Influence of temperature-induced copper diffusion on degradation of selective chromium oxy-nitride solar absorber coatings. <i>Solar Energy Materials and Solar Cells</i> , 2016 , 145, 323-332	6.4	17
27	Heteroleptic Cyclopentadienyl-Amidinate Precursors for Atomic Layer Deposition (ALD) of Y, Pr, Gd, and Dy Oxide Thin Films. <i>Chemistry of Materials</i> , 2016 , 28, 5440-5449	9.6	23
26	Atomic Layer Deposition of Iridium Thin Films Using Sequential Oxygen and Hydrogen Pulses. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 15235-15243	3.8	23
25	Low-temperature atomic layer deposition of copper(II) oxide thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 01A109	2.9	18
24	External beam IBA set-up with large-area thin Si ₃ N ₄ window. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2016 , 380, 11-14	1.2	5
23	MANOS performance dependence on ALD Al ₂ O ₃ oxidation source. <i>Microelectronic Engineering</i> , 2016 , 159, 127-131	2.5	1
22	Proton induced gamma-ray production cross sections and thick-target yields for boron, nitrogen and silicon. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2016 , 378, 25-30	1.2	6
21	Nucleation and Conformality of Iridium and Iridium Oxide Thin Films Grown by Atomic Layer Deposition. <i>Langmuir</i> , 2016 , 32, 10559-10569	4	24
20	Selective etching of focused gallium ion beam implanted regions from silicon as a nanofabrication method. <i>Nanotechnology</i> , 2015 , 26, 265304	3.4	5
19	Atomic layer deposition of zirconium dioxide from zirconium tetrachloride and ozone. <i>Thin Solid Films</i> , 2015 , 589, 597-604	2.2	18
18	Inert ambient annealing effect on MANOS capacitor memory characteristics. <i>Nanotechnology</i> , 2015 , 26, 134004	3.4	15
17	Charge and current hysteresis in dysprosium-doped zirconium oxide thin films. <i>Microelectronic Engineering</i> , 2015 , 147, 55-58	2.5	3
16	(Et ₃ Si) ₂ Se as a precursor for atomic layer deposition: growth analysis of thermoelectric Bi ₂ Se ₃ . <i>Journal of Materials Chemistry C</i> , 2015 , 3, 4820-4828	7.1	12
15	Atomic layer deposition and characterization of Bi ₂ Te ₃ thin films. <i>Journal of Physical Chemistry A</i> , 2015 , 119, 2298-306	2.8	23

14	Atomic Layer Deposition of AlF ₃ Thin Films Using Halide Precursors. <i>Chemistry of Materials</i> , 2015 , 27, 604-611	9.6	27
13	Preparation and bioactive properties of nanocrystalline hydroxyapatite thin films obtained by conversion of atomic layer deposited calcium carbonate. <i>Biointerphases</i> , 2014 , 9, 031008	1.8	11
12	Atomic Layer Deposition of TiO ₂ and ZrO ₂ Thin Films Using Heteroleptic Guanidinate Precursors. <i>Chemical Vapor Deposition</i> , 2014 , 20, 209-216		5
11	Influence of microstructure on temperature-induced ageing mechanisms of different solar absorber coatings. <i>Solar Energy Materials and Solar Cells</i> , 2014 , 120, 462-472	6.4	31
10	Magnetic Properties of Polycrystalline Bismuth Ferrite Thin Films Grown by Atomic Layer Deposition. <i>Journal of Physical Chemistry Letters</i> , 2014 , 5, 4319-23	6.4	21
9	Stopping cross sections of atomic layer deposited Al ₂ O ₃ and Ta ₂ O ₅ and of Si ₃ N ₄ for ¹² C, ¹⁶ O, ³⁵ Cl, ⁷⁹ Br and ¹²⁷ I ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2013 , 300, 1-5	1.2	5
8	Cycloheptatrienyl-Cyclopentadienyl Heteroleptic Precursors for Atomic Layer Deposition of Group 4 Oxide Thin Films. <i>Chemistry of Materials</i> , 2012 , 24, 2002-2008	9.6	22
7	Atomic Layer Deposition of Antimony and its Compounds Using Dechlorosilylation Reactions of Tris(triethylsilyl)antimony. <i>Chemistry of Materials</i> , 2011 , 23, 247-254	9.6	40
6	Spin-glass magnetism of surface rich Au cluster film. <i>Applied Physics Letters</i> , 2011 , 99, 022503	3.4	3
5	Rare earth scandate thin films by atomic layer deposition: effect of the rare earth cation size. <i>Journal of Materials Chemistry</i> , 2010 , 20, 4207		29
4	Atomic layer deposition of ytterbium oxide using -diketonate and ozone precursors. <i>Applied Surface Science</i> , 2009 , 256, 847-851	6.7	18
3	Atomic layer deposition of Ge ₂ Sb ₂ Te ₅ thin films. <i>Microelectronic Engineering</i> , 2009 , 86, 1946-1949	2.5	58
2	A pyrazolate-based metalorganic tantalum precursor that exhibits high thermal stability and its use in the atomic layer deposition of ta(2)o(5). <i>Journal of the American Chemical Society</i> , 2007 , 129, 12370-1	16.4	36
1	Molecular Layer Deposition of Thermally Stable Polybenzimidazole-Like Thin Films and Nanostructures. <i>Advanced Materials Interfaces</i> , 2200370	4.6	